

Abstract Submitted  
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**Molecular-weight Dependent T<sub>g</sub> Depression of Silica-supported Poly(alpha-methyl styrene) Films**<sup>1</sup> OPHELIA TSUI, KUN GENG, Boston Univ — The glass transition temperature ( $T_g$ ) of poly( $\alpha$ -methyl styrene) (P $\alpha$ MS) films supported by silica is studied as a function of film thicknesses from 17 to 168 nm at three molecular weights of 1.3, 20 and 420 kg/mol. For the 20 and 420 kg/mol films, the glass transition temperature decreases with decreasing film thickness, consistent with previous results. But for the 1.3 kg/mol films, it becomes independent of the film thickness. We tentatively suggest the  $T_g$  depression to be caused by free volume excess at the polymer-air interface and that its influence diminishes at low enough molecular weights because of a chain stiffness effect.

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